

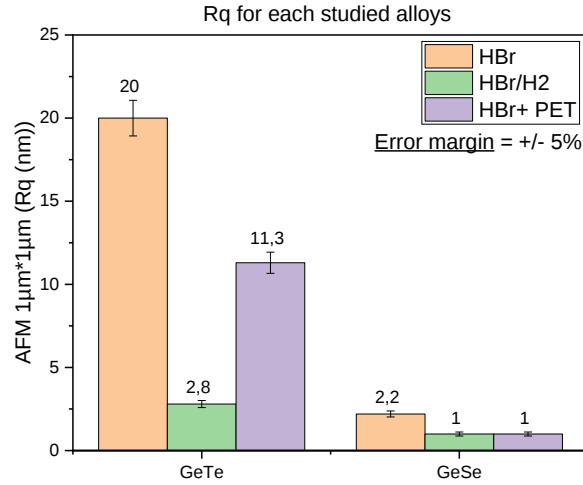


Figure 1: AFM measurement for surface roughness (R_q) for GeTe, GeSe after HBr, HBr/H₂ [50/50] and HBr + PET

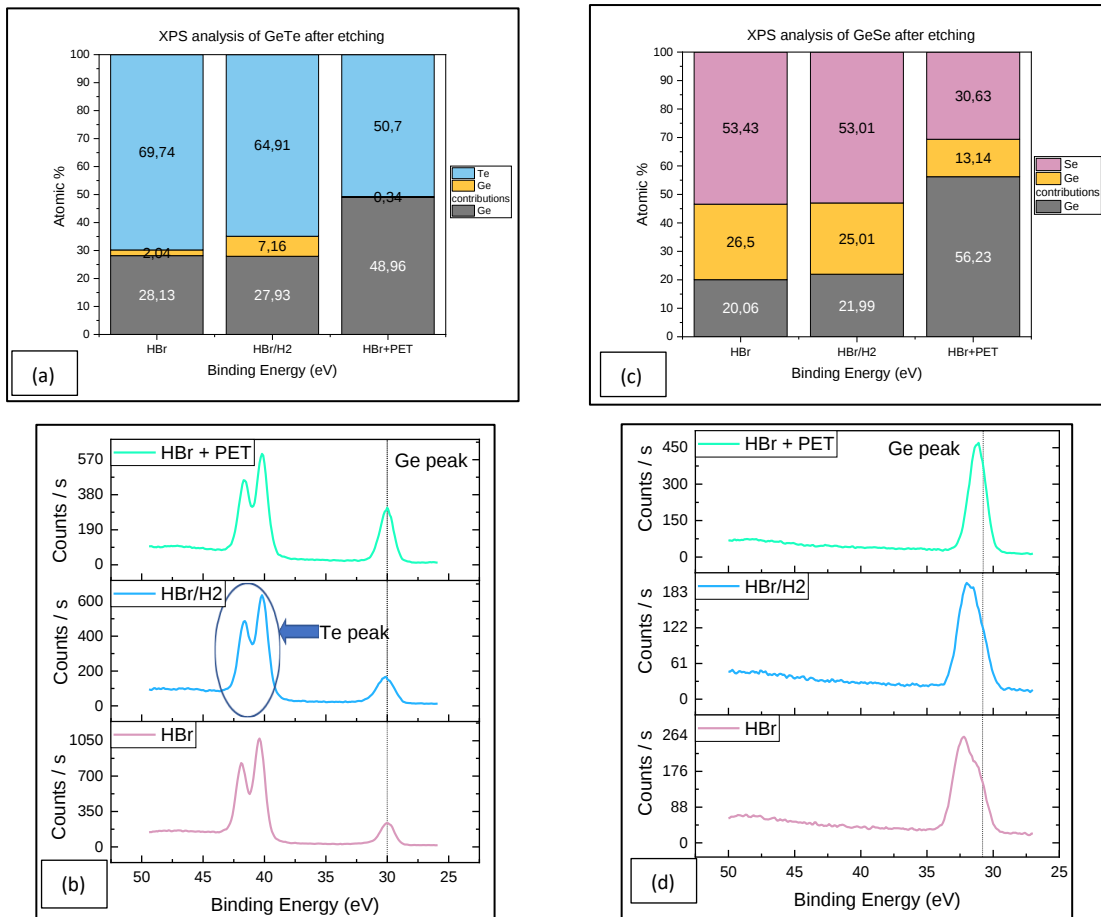


Figure 2: XPS measurement of GeTe (a-b) & GeSe (c-d) unpatterned wafers after HBr, HBr/H₂ [50/50] and HBr + PET